

U.S. Department of Commerce, Patent and Trademark				Atty. Docket No.		Patent No.	
INFORMATION DISCLOSURE STATEMENT BY REQUESTOR				SENS.005US0		10/056,906	
				Applicant(s)			
(Use several sheets if necessary)				Wayne G. Renken			
				Filing Date		Group	
				January 24, 2002		2856	

U.S. Patent Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
COA	001	6,542,835	04/01/2003	Mundt			

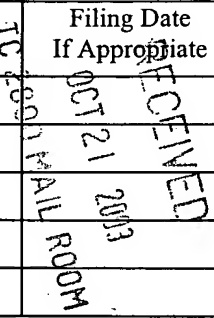
U.S. Published Patent Application Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
COA	002	2002/0193957	12/19/2002	Freed			
	003	2002/0172097	11/21/2002	Freed			
	004	2002/0177916	11/28/2002	Polla			
	005	2002/0177917	11/28/2002	Polla			
COA	006	2002/0161557	10/31/2002	Freed			

Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
COA	007	WO02/17030A2	02/28/2002	PCT				
COA	008	WO02/17030A3	02/28/2002	PCT				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)	
COA	009 Prov. Pat. App. No. 60/285,613 filed 04/19/2001; Freed et al.; "Firmware, Methods, Apparatus, and Computer Program Products for Wafer Sensors"
	010 Prov. Pat. App. No. 60/285,439 filed 04/19/2001; Freed et al.; "Methods Apparatus, and Computer Program Products for Obtaining Data for Process Operation, Optimization, Monitoring, and Control"
	011 Freed et al.; "Autonomous On-Wafer Sensors for Process Modeling, Diagnosis; and Control", IEEE Transactions on Semiconductor Manufacturing, Vol. 14, No. 3, Aug. 2001, pp. 255-264.
COA	012 Freed; "Wafer-Mounted Sensor Arrays for Plasma Etch Processes", Dissertation, Univ. of CA, Berkeley, Fall 2001

Examiner	COA	Date Considered	1/6/2004
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.



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U.S. Patent Documents							
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CPA	001	6,553,277	4/2003	Yagisawa			
	002	6,378,378	4/2002	Fisher			
	003	6,313,903	11/2001	Ogata			
CPA	004	6,472,240	10/2002	Akram			

U.S. Published Patent Application Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
CPA	005	2001/0014520	8/2001	Usui			
CPA	006	2002/0109590	8/2002	Parsons			

Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
CPA	007	WO00/68986	2000	PCT				
CPA	008	EP 1 014 437 A2	6/2000	EP				

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)	
CPA	009 International Search Report, PCT/US03/00751, 08/01/2003.
CPA	010 Baker et al., "A Novel <i>In Situ</i> Monitoring Technique for Reactive Ion Etching Using a Surface Micromachined Sensor," IEEE Transactions on Semiconductor Manufacturing, Vol. 11, No. 2, May 1998, pp. 254-64.

Examiner	CPA	Date Considered	1/6/2004
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